

► ALD Systems & Components

ALD Series—We offer stand-alone ALD systems for basic research or completely integrated deposition systems for complex R&D applications. All of our ALD system platforms feature full process control, integrated pumping, pressure measurement, and gas delivery packages optimized for your specific process.



■ ALD-150L

Compact computer controlled system features a high performance, efficient viscous flow ALD reactor.

- Small footprint
- Stainless steel chamber
- Accommodates 6" substrates
- Heating to 500° C
- Heated lines to 200° C
- Remote plasma option
- Load lock/substrate transfer option
- Bubbler option - with closed loop control
- Fully exhausted cabinet



■ ALD-200L

Computer controlled rack-sized system which supports advanced ALD research.

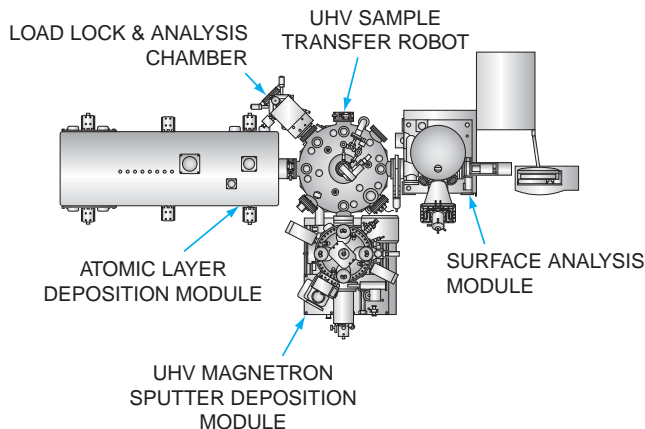
- Featuring a viscous flow ALD reactor
- Enclosed design accommodates a large number of reactant inputs
- Chamber accommodates up to 8" substrates
- Heating to 500° C
- Fully exhausted cabinet with gas interlocks
- Remote plasma option
- Load lock substrate transfer option
- Bubbler option - with closed loop control

➤ ALD Systems & Components

■ ALD-8000

Fully integrated computer controlled system supports a wide range of process enhancements and metallurgy tools to complement our ALD reactor - all within the vacuum environment.

- Fully exhausted cabinet with gas interlocks
- Stainless steel chamber
- Up to 8" substrates with up to 500° C heating
- Heated lines to 200° C
- Maximum number of reactants and gas inputs
- Full in-vacuum transfer capability through central distribution center to connected system and processes



■ ALD Reactant Chamber Design

The Kurt J. Lesker Company®'s ALD reactant chamber is designed for fast cycle times and maximum flexibility. The sample is loaded through a rectangular port in the chamber (either manually or utilizing the optional load lock) and positioned in the reactant chamber where the deposition takes place. Up to four precursor or gas inputs are introduced through the top plate. A fifth input is available through the plasma port.

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| <ul style="list-style-type: none"> • Stainless steel construction • Front loading port • Close proximity back side heating to 500° C • Substrates from small irregular pieces up to 200mm wafers • Analytical ports in reactor for in-situ analysis • Remote plasma option for low temperature process • Top mounted vapor delivery • Curtain gas flow design to speed cycle time and to minimize contamination on reactor walls and ellipsometry to reduce unwanted side reactions | <p>Optional</p> <ul style="list-style-type: none"> • Vacuum load lock • Remote plasma source • In-situ • RGA system • Ellipsometry package • Bubbler • 500° C substrate heating • Chamber heating to 150° C • Heated lines to 200° C • Dry pumping remote with plasma source |
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